

REMARKS

This Amendment is being filed in response to the Office Action mailed on October 28, 2008 which has been reviewed and carefully considered. Reconsideration and allowance of the present application in view of the amendments made above and the remarks to follow are respectfully requested.

Claims 1-4 remain in this application, where claim 4 had been added and claim 1 is independent.

In the Office Action, the Examiner objected to claim 1 for certain informalities. Without agreeing with the position forwarded in the Office Action and in the interest of advancing prosecution, claim 1 has been amended to remove the informalities noted by the Examiner. Accordingly, withdrawal of the objection to claim 1 is respectfully requested.

In the Office Action, claims 1 and 4 are rejected under 35 U.S.C. §103(a) over U.S. Patent Application Publication No. 2005/0120902 (Adams) in view of an article entitled "Silicon Transfer During Microcontact Printing" (Glasmaster). Further,

claims 2-3 are rejected under 35 U.S.C. §103(a) over Adams and Glasmaster in view of an article entitled "Edge Transfer Lithography of Molecular and Nanoparticle Materials" (Cherniavskaya). It is respectfully submitted that claims 1-4 are patentable over Adams, Glasmaster and Cherniavskaya for at least the following reasons.

Both Adams and Cherniavskaya appear to be related, e.g., both including the identical FIG 1, and are directed to edge transfer lithography, where a stamp 10 is made of polydiemthoxysilane (PDMS). As shown in FIG 1A and described in paragraph [0025] of Adams, the Adams stamp 10 has stamp or contact surfaces 14 with edges 19 between recesses 12. As clearly shown in FIG 1A, Adams discloses transferring ink to a single substrate made of SiO₂, where the stamp 10 makes a single contact with the surface 18 of the single substrate.

Similar to Adams and Glasmaster, Cherniavskaya also merely discloses a PDMS stamp where ink is transferred by having the stamp make a single contact with a single substrate, as shown in FIG 6, on page 5482.

In stark contrast, the present invention as recited in independent claim 1, amongst other patentable elements recites (illustrative emphasis provided):

providing an elastomeric stamp having a bulk surface and at least one feature protruding from the bulk surface, the protruding feature having a contact surface and an edge extending from the contact surface to the bulk surface, the protruding feature and the bulk surface carrying a barrier layer; ...

providing a first substrate with a surface having a higher affinity for the ink than the barrier layer; contacting the contact surface of the protruding feature with the surface of the first substrate;

transferring the ink from the contact surface of the protruding feature to the surface of the first substrate;

removing the elastomeric stamp from the surface of the first substrate;

providing a second substrate with a surface having a higher affinity for the ink than the barrier layer;

contacting the contact surface of the protruding feature with the surface of the second substrate; and

providing the surface of the second substrate with an ink pattern by transferring the ink from the edge of the protruding feature to the surface of the second substrate.

Transferring the ink from the edge by contacting a first substrate and then contacting a second substrate is nowhere disclosed or suggested in Adams, Glasmaster, Cherniavskaya, and

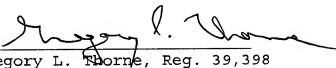
combination thereof. Rather, Adams, Glasmaster and Cherniavskaya merely disclose contacting a single substrate.

Accordingly, it is respectfully requested that independent claim 1 be allowed. In addition, it is respectfully submitted that claims 2-4 should also be allowed at least based on their dependence from independent claim 1 as well as their individually patentable elements.

In addition, Applicants deny any statement, position or averment of the Examiner that is not specifically addressed by the foregoing argument and response. Any rejections and/or points of argument not addressed would appear to be moot in view of the presented remarks. However, the Applicants reserve the right to submit further arguments in support of the above stated position, should that become necessary. No arguments are waived and none of the Examiner's statements are conceded.

In view of the above, it is respectfully submitted that the present application is in condition for allowance, and a Notice of Allowance is earnestly solicited.

Respectfully submitted,

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